EV372453882

Inventor:

H. Daniel Dulman et al.

Title:

Methods of Printing Structures

Assignee:

Micron Technology, Inc.

Serial No.: Filed Herewith

Filing Date: Filed Herewith

INFORMATION DISCLOSURE STATEMENT PURSUANT TO 37 C.F.R. §§1.56, 1.97 AND 1.98

In compliance with 37 C.F.R. §§1.56, 1.97 and 1.98, your attention is directed to the references listed on the attached Form PTO-1449.

The listed references were cited by, or submitted to, the Office in the parent, co-pending application of the above-identified application. The above-identified application is a divisional of co-pending application Serial No. 10/226,005, filed August 21, 2002. Such prior disclosure is sufficient for the above-identified application as far as copies of the references are 37 C.F.R. §1.98(d) and MPEP §609(2). No admission is made regarding whether all the submitted references are prior art.

Citation of these references is respectfully requested.

Respectfully submitted,

David G. Latwesen, Ph.D.

Reg. No. 38,533

WELLS, ST. JOHN P.S.

EV372453

Form PTO-1449

U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

ATTY. DOCKET NO. MI22-2513 SERIAL NO. Filed Herewith

LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)

APPLICANT H. Daniel Dulman et al.

					FILING DATE GROUP Filed Herewith Unknown				
	· ·		1	U.S. PATENT DOCUMENTS					
Examiner Initial		Document Number	Date	Name		Class Subclass		Filing Date If Appropriate	
	АА	5,308,721	05/94	Garofalo et al.					
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